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(54) Title: PROCESS FOR PRODUCING BISPHENOL A

(57) Abstract: A process for producing bisphenol A, including (a) reacting a feed containing phenol and acetone in the presence of an acid catalyst to obtain a product stream; (b) distilling the product stream to remove acetone and to obtain a bottom stream containing bisphenol A, phenol and an acid contaminant; (c) crystallizing the bottom stream to obtain crystals of adduct of bisphenol A with phenol; (d) removing phenol from the crystals to yield bisphenol A; (e) recycling a portion of the mother liquor to step (a); (f) treating remainder portion of the mother liquor to purge a residual tar and to recover a purified liquor, the amount of the reminder portion being 0.5-5 parts by weight per 100 parts by weight of the mother liquor; (g) recycling the purified liquor to step (a); and (h) treating at least one of (i) at least part of the feed, (ii) at least part of the product stream and (iii) at least part of the portion of the mother liquor to remove the acid contaminant contained therein, so that the concentration of the acid contaminant in the stream to be supplied to step (c) is maintained within a range of 0.001-0.5 meq/L.